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## (54) PLASMA PROCESSING DEVICE

## (57)Abstract:

**PURPOSE:** To improve a useful period of a quartz member also to perform a stable plasma process, by confining plasma, generated in a processing vessel, in a prescribed part, and protecting a quartz member, provided in the processing vessel, from corrosion by the plasma for generating the plasma of high density.

**CONSTITUTION:** A quartz-made annular shield ring 25 is fitted to a peripheral part of an upper part electrode 2, to provide a quartz-made annular focus ring 19 in a peripheral part of a wafer W on a lower part electrode 3. Alumina system ceramic layers 20, 26, which are a member having corrosion resistance higher than quartz relating to plasma, are provided in a surface relating to the plasma of these quartz-made rings.

